

INFORMATION DISCLOSURE STATEMENT BY APPLICANT Sheet 1 of 1	Application Number: 10/646,526 Filing Date: August 22, 2003 First Named Inventor: Kenneth COLLINS, et al. Group Art Unit: 1763 Examiner Name: Maureen G. Arancibia Attorney Docket Number: 006915 P08
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Examiner Initials	Document No	Publication Date	Name of Patentee or Applicant of Cited Document	Class	Subclass	Filing Date
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Examiner's Signature: *Maureen G. Arancibia*

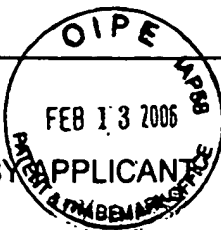
Date Considered: 03/02/2006

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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INFORMATION
DISCLOSURE
STATEMENT BY APPLICANT

Sheet 1 of 1



Application Number: 10/646,526
Filing Date: 08/22/2003
First Named Inventor: Kenneth COLLINS, et al.
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Examiner Name: Maureen G. Arancibia
Attorney Docket Number: 006915/P08

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